

<b>Notice of References Cited</b>	Application/Control No. 10/585,845		Applicant(s)/Patent Under Reexamination MISAWA ET AL.	
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#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
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#### FOREIGN PATENT DOCUMENTS

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#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	VENKATAKRISHNAN et al, Laser Writing Techniques for Photomask Fabrication Using a Femtosecond laser, 2002, Applied Phycsis A Materials Science adn Processing, Vol. 74, pages 493-496
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